

MICRON.098CDV2

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Basceri et al.
App. No.	:	Unknown
Filed	:	Herewith
For	:	HAZE-FREE BST FILMS
Examiner	:	Unknown
Group Art Unit	:	Unknown

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

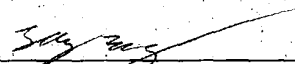
Dear Sir:

Enclosed is form PTO-1449 listing 15 references that are also enclosed. This Information Disclosure Statement is being filed within three months of the filing date of this application or upon filing if this is a CPA or RCE, and no fee is required in accordance with 37 C.F.R. § 1.97(b)(1), (b)(2), or (b)(4).

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 6/27/03

By:   
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FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  <b>INFORMATION DISCLOSURE STATEMENT          BY APPLICANT</b>  (USE SEVERAL SHEETS IF NECESSARY)	ATTY. DOCKET NO. MICRON.098CDV2	APPLICATION NO. Unknown
	APPLICANT Basceri et al.	
	FILING DATE Herewith	GROUP Unknown

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	1	5,335,138	8/2/94	Sandhu et al.			
	2	5,406,445	4/11/95	Fujii et al.			
	3	5,506,166	4/9/96	Sandhu et al.			
	4	5,717,234	2/10/98	Si et al.			
	5	5,781,404	7/14/98	Summerfelt et al.			
	6	5,783,253	7/21/98	Roh			
	7	5,889,299	3/30/99	Abe et al.			
	8	5,973,911	10/26/99	Nishioka			
	9	6,010,931	1/4/00	Sun et al.			
	10	6,117,482	9/12/00	Kawahara et al.			
	11	6,136,639	10/24/00	Seon			
	12	6,319,764 B1	11/20/01	Basceri et al.			

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
	13	Hiroimi Itoh et al., "Integration of BST Thin Film for Dram Fabrication", Integrated Ferroelectrics, 1995 Vol. 11, pp 101-109
	14	C. Basceri, "An Important Failure Mechanism in MOCVD (Ba,Sr)TiO <sub>3</sub> Thin Films: Resistance Degradation", Ferroelectric Thin Films IV, Materials Research Society, Symposium Proceedings Volume 493, 1998, pp. 9-14
	15	Chung Ming Chu and Pang Lin, "Electric Properties and Crystal Structure of a (Ba,Sr)TiO <sub>3</sub> Films Prepared at Low Temperatures on a LaNiO <sub>3</sub> Electrode by Radio-Frequency Magnetron Sputtering", Appl. Phys. Lett., Vol. 70 (2), 13 January 1997, pp.249-51
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061903

EXAMINER	DATE CONSIDERED
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	

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	15	Chung Ming Chu and Pan Lin, "Electrical Properties and Crystal Structure of a (Ba Sr) TiO <sub>3</sub> Films Prepared at Low Temperatures on a LaNiO <sub>3</sub> Electrode by Radio-Frequency Magnetron Sputtering," Appl. Phys. Lett., Vol. 70 (2), 13 January 1997, pp. 249-51
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